Patent approval by the Japan Patent Office (JPO)

XTPL S.A., a joint stock company with its registered office in Wrocław

Legal basis:
Article 17(1) MAR - confidential information

The Management Board of XTPL ("Issuer", "Company", "XTPL") hereby reports that on 17 May 2024 it received the issue notification sent by the Japan Patent Office which guarantees that the patent will be granted for an invention "Methods of dispensing a metallic nanoparticle composition form a nozzle onto a substrate".

The application procedure for this patent was initiated on 28 July 2020. This is also the date when patent protection started for the invention. The final formal requirement for obtaining the patent is to pay the necessary fee. Should the requirement not be met, the Company will communicate this in a separate current report.

The patent protection will increase the value of the potential commercialization of the Company's technology with respect to the Issuer's technological solutions for the next generation electronics market. The reported event confirms continued delivery of the Company's strategy of building a patent cloud for its proprietary technology and products, which will contribute to building the Issuer's credibility among potential industrial clients.

In view of the above, and considering the confirmation of uniqueness of the Company's technological solutions, and then the outlook for the Issuer's perception by investors, the Issuer's Management Board has decided that the notice of allowance and information related to allowed claims should be deemed confidential information. For this reason, in the opinion of the Management Board, the information meets the criteria set out in Article 7(1) of the MAR.

Jacek Olszański
Management Board Member